Synthesis and spectroscopic characterization of tris(*tert*-butoxy)siloxy titanium and hafnium complexes: Molecular precursor to [M/Si/O (M = Ti, Hf)] materials

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ABSTRACT

The reaction of one equivalent of metallocene dichloride Cp_2MCl_2 (M = Ti, Hf) with two molar equivalents of sodium salt of tri(*tert*-butoxy)siloxane, ('BuO)₃SiONa, in toluene yields $Cp_2Ti[OSi(O'Bu)_3]_2$ (1) and $Cp_2Hf[OSi(O'Bu)_3]_2$ (2). These compounds were characterized by analytical and spectroscopic techniques (C/H/N analysis, FT-IR, NMR, EI-MS, and thermal analysis). An independent thermolysis of 1 and 2 at low temperature resulted in the formation of the corresponding metal silicates $MO_2 \cdot 2 SiO_2$ [M = Ti (3) and Hf (4)] as evidenced by infrared spectroscopy, powder X-ray diffraction analysis (PXRD), and scanning electron microscopy (SEM). These thermally stable amorphous metal silicate materials (3 and 4), albeit exhibiting moderate surface areas, are found to be microporous by N₂ adsorption studies. UV-vis-NIR spectroscopy shows low energy band gap $E_g = 2.63$ eV for 3 and 2.99 eV for 4 due to the silicon oxide mixed with the corresponding transition metal oxides. The photocatalytic activity of titanium silicate material (3) has been explored in terms of degradation of methylene blue.

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GRAPHICAL ABSTRACT



Introduction

The development of advanced materials with tailored properties frequently requires low-temperature methods to permit the formation of metastable structures.^{1–3} Sol-gel method has attracted great interest as a low-temperature route for the synthesis of metal oxide materials *via* the hydrolysis/condensation of alkoxide precursors.^{4,5} However, there are still difficulties in controlling the atomic structures of sol-gel derived products, because the rates of hydrolysis for different metal precursors in a polar solvent vary drastically.^{6,7} An alternative approach for the synthesis of homogenous metal oxide materials implies the use of single-source molecular precursors that exhibit advantages including well-defined stoichiometries, efficient incorporation of building blocks, kinetically controlled reaction pathway and low temperature routes to metastable structures. In this context, Tilley et al. studied the use of single source precursors of metal siloxanes for the synthesis of corresponding silicate materials at elevated temperature. For example, transition-metal and main-group metal complexes containing the oxygen-rich ligand $-OSi(O^tBu)_3$ have been used as single-source precursors to produce homogeneous metal silicate materials (M/Si/O) due their clean thermal decomposition at low temperatures ($\sim 300^{\circ}C$) *via* the elimination of isobutene and water.⁸⁻¹² Thermolytic molecular precursor approach is a promising method to generate metal silicate materials by homogeneous incorporation of the metal into the structure, particularly at high metal loadings. Such high dispersions are difficult to achieve by wet impregnation methods, because metal oxide domains tend to form under aqueous conditions. Over the past decade few research group have been investigating the synthesis of metal silicate

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